

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants:	Schwarzl, <i>et al.</i>	Docket No.:	QIM 2004 P 50143 US
Serial No.:	10/812,411	Art Unit:	1763
Filed:	March 30, 2004	Examiner:	Moore, Karla A.
For:	EUV Lithography System and Chuck for Releasing Reticle in a Vacuum Isolated Environment		

Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

AMENDMENT

Dear Sir:

The following amendments and remarks are presented in response to the Examiner's
Office Action mailed June 12, 2007. Please amend the above-referenced application as follows.